JUL 2 3 2008 2 Attorne Deckar 0. 033082 M 275

I AF

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants

Kazuhide HASEBE, et al.

Confirmation No.: 6774

U.S. Serial No.

10/552,262

Filed

Examiner

Lan Vinh

October 5, 2005

Group Art Unit

1792

For

SILICON DIOXIDE FILM REMOVING METHOD AND

PROCESSING SYSTEM

AFTER FINAL AMENDMENT UNDER 37 C.F.R. § 1.116

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 MAIL STOP: AF

Sir:

In response the Final Office Action mailed on April 25, 2008, for which the time for response is set to expire July 25, 2008, please amend the above-identified application as set forth below and consider the following remarks.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 5 of this paper.